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SEARCH REQUEST FORM

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Title of Invention: Metho			Aluin mailie
Inventors (please provide full name	es): Mood	Jeffrey Rie	ley, Robert Hise
English Dilait Pitt	3/1988		
Earliest Priority Filing Date:			· ·
For Sequence Searches Only Please i appropriate serial number.	nclude all pertinent informa	tion (parent, child, divisional, or iss	ued patent numbers) along with the
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Date Completed:	Litigation	Lexis/Nexis_	
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PTO-1590 (8-01)

Curr nt session 11/09/2002

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Search statement

Query/Command: US6036872/PN

** SS 1: Results 1

Search statement 2

Query/Command: PRT FULL NONSTOP LEGALALL

1/1 PLUSPAT - @QUESTEL-ORBIT

PN - US6036872 A 20000314 [US6036872]

TI - (A) Method for making a wafer-pair having sealed chambers

PA - (A) HONEYWELL INC (US)

IN - (A) WOOD R ANDREW (US); RIDLEY JEFFREY A (US); HIGASHI ROBERT E (US)

AP - US5264598 19980331 [1998US-0052645]

PR - US5264598 19980331 [1998US-0052645]

IC - (A) C23F-001/00

EC - B81B-001/00 H01L-027/16

PCL - ORIGINAL (O): 216002000; CROSS-REFERENCE (X): 216024000 216033000 216039000 216056000 438054000 438456000 438700000 438703000

DT - Corresponding document

CT - US4701424; US5366587; US5528452; US5585311; US5851631

STG - (A) United States patent

AB - A method for fabricating a wafer-pair having at least one recess in one wafer and the recess formed into a chamber with the attaching of the other wafer which has a port plugged with a deposited layer on its external surface. The deposition of the layer may be performed in a very low pressure environment, thus assuring the same kind of environment in the sealed chamber. The chamber may enclose at least one device such as a thermoelectric sensor, bolometer, emitter or other kind of device. The wafer-pair typically will have numerous chambers, with devices, respectively, and may be divided into a multiplicity of chips.

UP - 2000-13

1/1 LGST - ©LEGSTAT

PN - US 6036872 [US6036872]

AP - US 52645/98 19980331 [1998US-0052645]

DT - US-P

ACT - 19980331 US/AE-A

APPLICATION DATA (PATENT)

US 52645/98 19980331 [1998US-0052645]

20000314 US/A

PATENT

20020326 US/RF

REISSUE APPLICATION FILED

20011203

UP - 2002-14

1/1 CRXX - @CLAIMS/RRX

PN - 6,036,872 A 20000314 [US6036872]

PA - Honeywell Inc

ACT - 20011203 REISSUE REQUESTED

ISSUE DATE OF O.G.: 20020326

REISSUE REQUEST NUMBER: 10/007288

EXAMINATION GROUP RESPONSIBLE FOR REISSUEPROCESS: 1753

Reissue Patent Number:

1/1 PAST - ©Thomson Derwent

AN - 200213-001635

PN - 6036872 A [US6036872]

OG - 2002-03-26

ACT - REISSUE APPLICATION FILED

Query/Command: FILE INPADOC

PLUSPAT - Time in minutes : 0,70 The cost estimation below is based on Questel's standard price list Estimated cost : 1.54 USD Records displayed and billed Estimated cost : 1.10 USD Cost estimated for the last database search : 2.64 USD Estimated total session cost 3.23 USD - Time in minutes : The cost estimation below is based on Questel's standard price list Estimated cost : 0.15 USD Records displayed and billed Estimated cost : 0.57 USD Legal-Status informations Estimated cost : 4.92 USD Cost estimated for the last database search : 5.64 USD Estimated total session cost 8.87 USD - Time in minutes : 0,07 The cost estimation below is based on Questel's standard price list Estimated cost : 0.10 USD Records displayed and billed : 1 Estimated cost : 5.00 USD Legal-Status informations Estimated cost : 4.92 USD Cost estimated for the last database search : 10.02 USD Estimated total session cost 18.89 USD - Time in minutes: 0,06 The cost estimation below is based on Questel's standard price list Estimated cost : 0.11 USD Records displayed and billed :

Estimated cost : 5.61 USD Legal-Status informations Estimated cost : 4.92 USD Cost estimated for the last database search : 10.64 USD Estimated total session cost 29.53 USD

- Time in minutes : 0,02

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Search statement 1

Query/Command: FAM US6036872/PN

1 Patent Groups

** SS 1: Results 5

Search statement 2

Query/Command: FAMSTATE NONSTOP

1/5 INPADOC - ©INPADOC

PN CA 2326677 AA 19991007 [CA2326677]

A METHOD OF MAKING A WAFER-PAIR HAVING SEALED CHAMBERS TI

LA **ENG**

WOOD R ANDREW [US]; RIDLEY JEFFREY A [US]; HIGASHI ROBERT E [US] IN

PA HONEYWELL INC (US)

CA 2326677/99-A 19990330 [1999CA-2326677] AP

PR US 52645/98-A 19980331 [1998US-0052645]

WO 9906890/99(US)-W 19990330 [1999WO-US06890]

IC H01L-027/16; G01J-005/20

1/1 LEGALI - ©LEGSTAT

PN CA 2326677 [CA2326677]

DT CA-P

ACTE -20000929 CA/REFW-P

CORRESPONDS TO PCT APPLICATION

<WO 9950913> [WO9950913]

UP 2001-11 2/5 INPADOC - ©INPADOC

PN - EP 1070353 A1 20010124 [EP1070353]

TI - A METHOD FOR MAKING A WAFER-PAIR HAVING SEALED CHAMBERS

LA - ENG

IN - WOOD R ANDREW [US]; RIDLEY JEFFREY A [US]; HIGASHI ROBERT E [US]

PA - HONEYWELL INC [US]

AP - EP 99914273/99-A 19990330 [1999EP-0914273]

PR - WO 9906890/99(US)-W 19990330 [1999WO-US06890]

US 52645/98-A 19980331 [1998US-0052645]

IC - H01L-027/16; G01J-005/20

DS - DE* FR* GB*

1/1 LEGALI - ©LEGSTAT

PN - EP 1070353 [EP1070353]

AP - EP 99914273/99 19990330 [1999EP-0914273]

DT - EP-P

ACTE - 19990330 EP/AE-A

EP-APPLICATION

EP 99914273/99 19990330 [1999EP-0914273]

20010124 EP/AK-A1 [+]

DESIGNATED CONTRACTING STATES IN AN APPLICATION WITH SEARCH

REPORT: DE FR GB

20010124 EP/A1 [+]

PUBLICATION OF APPLICATION WITH SEARCH REPORT

20010124 EP/17P [+]

REQUEST FOR EXAMINATION FILED

20000928

UP - 2001-04

3/5 INPADOC - ©INPADOC

PN - JP 2002510865 T2 20020409 [JP2002510865]

AP - JP 2000541738/00-A 19990330 [2000JP-0541738]

PR - US 52645/98-A 19980331 [1998US-0052645]

WO 9906890/99(US)-W 19990330 [1999WO-US06890]

IC - H01L-037/02; G01J-001/02

4/5 INPADOC - @INPADOC

PN - US 6036872 A 20000314 [US6036872]

TI - METHOD FOR MAKING A WAFER-PAIR HAVING SEALED CHAMBERS

IN - WOOD R ANDREW [US]; RIDLEY JEFFREY A [US]; HIGASHI ROBERT E [US]

PA - HONEYWELL INC [US]

AP - US 52645/98-A 19980331 [1998US-0052645]

PR - US 52645/98-A 19980331 [1998US-0052645]

IC - C23F-001/00

1/1 LEGALI - ©LEGSTAT

PN - US 6036872 [US6036872]

AP - US 52645/98 19980331 [1998US-0052645]

DT - US-P

ACTE - 19980331 US/AE-A

APPLICATION DATA (PATENT)

US 52645/98 19980331 [1998US-0052645]

20000314 US/A

PATENT

20020326 US/RF

REISSUE APPLICATION FILED

20011203

UP - 2002-14

5/5 INPADOC - ©INPADOC

PN - WO 9950913 A1 19991007 [WO9950913]

TI - A METHOD OF MAKING A WAFER-PAIR HAVING SEALED CHAMBERS

LA - ENG

IN - WOOD R ANDREW; RIDLEY JEFFREY A; HIGASHI ROBERT E

PA - HONEYWELL INC [US]

AP - WO US 9906890/99(US)-A 19990330 [1999WO-US06890]

PR - US 52645/98-A 19980331 [1998US-0052645]

IC - H01L-027/16; G01J-005/20

DS - CA* JP* AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE

1/3 LEGALI - ©LEGSTAT

PN JP 541738/2000

AP JP 541738/2000 0 [2000JP-0541738]

DT JP-A

ACTE -20001002 JP/REFW-P

CORRESPONDS TO PCT APPLICATION

<WO 9950913> WO9950913

UP 2002-09

2/3 LEGALI - ©LEGSTAT

PN CA 2326677 [CA2326677]

DT CA-P

ACTE -20000929 CA/REFW-P

CORRESPONDS TO PCT APPLICATION

<WO 9950913> [WO9950913]

UP 2001-11

3/3 LEGALI - ©LEGSTAT

PN WO 9950913 [WO9950913]

WO 9906890/99(US) 19990330 [1999WO-US06890] AP

DT WO-P

ACTE -19990330 WO/AE-A

APPLICATION DATA

WO 9906890/99(US) 19990330 [1999WO-US06890]

19991007 WO/AK-A1 [+]

DESIGNATED STATES CITED IN A PUBLISHED APPLICATION WITH SEARCH

REPORT CA JP

19991007 WO/AL-A1 [+]

DESIGNATED COUNTRIES FOR REGIONAL PATENTS CITED IN A PUBLISHED APPLICATION WITH SEARCH REPORT

AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE

19991007 WO/A1 [+]

PUBLICATION OF THE INTERNATIONAL APPLICATION WITH THE

INTERNATIONAL SEARCH REPORT

19991201 WO/121

EP: THE EPO HAS BEEN INFORMED BY WIPO THAT EP WAS DESIGNATED IN THIS APPLICATION

19991216 WO/DFPE

REQUEST FOR PRELIMINARY EXAMINATION FILED PRIOR TO EXPIRATION OF 19TH MONTH FROM PRIORITY DATE

20000929 WO/ENP-AA

20000929 WO/ENP-AA ENTRY INTO THE NATIONAL PHASE IN: <CA 2326677>

20001002 WO/ENP-A ENTRY INTO THE NATIONAL PHASE IN: <JP 00541738>

UP - 2002-09

PATNO IS 6036872

DATE: SEPTEMBER 11, 2002 LIBRARY: PATENT FILE: ALL

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For further explanation, press the H key (for HELP) and then the ENTER key.

LEVEL 1 - 1 PATENT

i . . .

1. 6036872 , March 14, 2000 , Method for making a wafer-pair having sealed chambers , Wood, R. Andrew, Bloomington, MN; Ridley, Jeffrey A., Burnsville, MN; Higashi, Robert E., Shorewood, MN, 00052645 (), Honeywell Inc., Minneapolis, MN

CORE TERMS: wafer, layer, vacuum, sub, detector, chamber, cavity, deposited, angstrom, port ...

LEVEL 1 - 1 OF 1 PATENT

UNITED STATES PATENT AND TRADEMARK OFFICE GRANTED PATENT

6036872

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March 14, 2000

Method for making a wafer-pair having sealed chambers

REISSUE: December 3, 2001 - Reissue Application filed Dec. 3, 2001 (O.G. Mar. 26, 2002) Ex. Gp.: 1753; Re. S.N. 10/007,288March 26, 2002

APPL-NO: 00052645 ()

FILED-DATE: March 31, 1998

GRANTED-DATE: March 14, 2000

CORE TERMS: wafer, layer, vacuum, sub, detector, chamber, cavity, deposited,

angstrom, port ...

ENGLISH-ABST:

. Y

A method for fabricating a wafer-pair having at least one recess in one wafer and the recess formed into a chamber with the attaching of the other wafer which has a port plugged with a deposited layer on its external surface. The deposition of the layer may be performed in a very low pressure environment, thus assuring the same kind of environment in the sealed chamber. The chamber may enclose at least one device such as a thermoelectric sensor, bolometer, emitter or other kind of device. The wafer-pair typically will have numerous chambers, with devices, respectively, and may be divided into a multiplicity of chips.

6036872 OR 6,036,872

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